Amendments to the Specification:

Please replace the paragraph beginning on page 7, line 4, with the following rewritten paragraph:

Thus, as illustrated in figures 6 to 9, the electrolyte 5 comprising at least one lithiated compound, for example a lithium and phosphorus oxynitride (LiPON), is formed on the surface 1a of the substrate 1 provided with the first and second current collectors 2a and 2b and with the cathode 3. The electrolyte 5 covers the whole of the ~~anode 3,~~ cathode 3, a part of the surface 1a of the substrate 1 arranged between the first and second current collectors 2a and 2b and a part of the second current collector 2b (figure 9). As represented in figure 6, to form the electrolyte 5 and in particular to define the shape and position thereof, an electrolytic thin layer 5a comprising at least one lithiated compound and having a thickness of about 1mm is deposited on the whole of the surface 1a of the substrate 1 provided with the current collectors 2a and 2b and with the cathode 3. Deposition of the electrolytic thin layer 5a is for example achieved by physical vapor deposition. To protect the lithiated compound contained in the electrolytic thin layer 5a, a first protective thin layer 6a constituted by a material that is chemically inert with regard to lithium and a first masking thin layer 7a are successively deposited on the whole of the electrolytic thin layer 5a, thus forming a stack called double masking. The double masking is for example achieved by Plasma Enhanced Chemical Vapor Deposition (PECVD).